

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:	David Alan Baldwin	:	
	and Todd L. Hylton	:	
Serial No.:	10/812,409	:	Attorney Docket No.: 53757-5013
Filed:	March 29, 2004	:	Art Unit: 1753
For:	System And Method For Performing	:	
	Sputter Etching Using Independent	:	
	Ion And Electron Sources And A	:	
	Substrate Biased With An A-	:	
	Symmetric Bi-Polar DC Pulse	:	
	Signal	:	

RESPONSE TO OFFICIAL ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

The following is submitted in response to the Official Action dated July 23, 2007.